

S. Feltle
9/29/01

Docket No.: 202603US2DIV

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

#2/Pa

IN RE APPLICATION OF:

Tetsuya SADA et al. : EXAMINER:

SERIAL NO: New Divisional Application

FILED: Herewith :

FOR: COOLING DEVICE AND COOLING : GROUP ART UNIT:
METHOD

PRELIMINARY AMENDMENT

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

Prior to examination on the merits, please amend this application as shown in the attachment:

IN THE SPECIFICATION

Page 2, lines 8-12, replace with the following paragraph:

In addition, in the photolithography step described above, the cooling step must be performed for one substrate several times. For this reason, in order to increase a throughput, one important problem is to shorten a time for the cooling process.

Page 20, line 16 through page 21, line 22, replace with the following paragraph:

The processing steps shown in FIG. 10 will be described below. In the processing steps, as in the processing steps shown in FIG. 9, before the glass substrate G is placed on the placing table 2, in step S30, a coolant having a predetermined temperature, e.g., 23°C is supplied from the second coolant supply means 31 into the coolant path 28 of the placing